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## Sommario/riassunto

Integrated circuits, and devices fabricated using the techniques developed for integrated circuits, have steadily gotten smaller, more complex, and more powerful. The rate of shrinking is astonishing - some components are now just a few dozen atoms wide. This book attempts to answer the questions, "What comes next?? and "How do we get there?? Nanolithography outlines the present state of the art in lithographic techniques, including optical projection in both deep and extreme ultraviolet, electron and ion beams, and imprinting. Special attention is paid to related issues, such as the re

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